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(54) CVD synthesis of silicon nitride materials

(57) Low hydrogen-content silicon nitride materials are deposited by a variety of CVD techniques, preferably thermal CVD and PECVD, using chemical precursors that contain silicon atoms, nitrogen atoms, or both. A preferred chemical precursor contains one or more N-

Si bonds. Another preferred chemical precursor is a mixture of a N-containing chemical precursor with a Si-containing chemical precursor that contains less than 9.5 weight % hydrogen atoms. A preferred embodiment uses a hydrogen source to minimize the halogen content of silicon nitride materials deposited by PECVD.

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DOCUMENTS CONSIDERED TO BE RELEVANT			CLASSIFICATION OF THE APPLICATION (Int.Cl.7)
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.7)
X	US 5 616 754 A (CLARK TERENCE ET AL) 1 April 1997 (1997-04-01) * column 3, line 1 - column 4, line 23 * * column 6, line 45-47 * ---	1-4,6-8, 12-18 5,9	C23C16/34 H01L21/318 C23C16/30
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The present search report has been drawn up for all claims			
Place of search	Date of completion of the search	Examiner	
THE HAGUE	26 October 2001	Castagné, C	
CATEGORY OF CITED DOCUMENTS		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document	
X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document			



European Patent
Office

Application Number

EP 01 30 3885

CLAIMS INCURRING FEES

The present European patent application comprised at the time of filing more than ten claims.

- Only part of the claims have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims and for those claims for which claims fees have been paid, namely claim(s):

- No claims fees have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims.

LACK OF UNITY OF INVENTION

The Search Division considers that the present European patent application does not comply with the requirements of unity of invention and relates to several inventions or groups of inventions, namely:

see sheet B

- All further search fees have been paid within the fixed time limit. The present European search report has been drawn up for all claims.

- As all searchable claims could be searched without effort justifying an additional fee, the Search Division did not invite payment of any additional fee.

- Only part of the further search fees have been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the inventions in respect of which search fees have been paid, namely claims:

- None of the further search fees have been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the invention first mentioned in the claims, namely claims:



DOCUMENTS CONSIDERED TO BE RELEVANT									
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			TECHNICAL FIELDS SEARCHED (Int.Cl.7)						
<p>The present search report has been drawn up for all claims</p> <table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td style="width: 33%; padding: 2px;">Place of search</td> <td style="width: 33%; padding: 2px;">Date of completion of the search</td> <td style="width: 33%; padding: 2px;">Examiner</td> </tr> <tr> <td style="padding: 2px;">THE HAGUE</td> <td style="padding: 2px;">26 October 2001</td> <td style="padding: 2px;">Castagné, C</td> </tr> </table>				Place of search	Date of completion of the search	Examiner	THE HAGUE	26 October 2001	Castagné, C
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THE HAGUE	26 October 2001	Castagné, C							
CATEGORY OF CITED DOCUMENTS		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document							
X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document									



The Search Division considers that the present European patent application does not comply with the requirements of unity of invention and relates to several inventions or groups of inventions, namely:

1. Claims: 1-16

Process for depositing a silicon nitride material from a vapor phase by thermal decomposition of a chemical precursor comprising one or more N-Si chemical bond, preferably selected from the group consisting of $(X_3Si)_3N$, $(X_3Si)N-N(SiX_3)_2$, $(X_3Si)N=N(SiX_3)$ and $(R_{3-m}SiX_m)_3N$ with $m=0,1$ or 2 and $X = F, Cl, Br, H$ or D and $R =$ methyl, ethyl, phenyl or tertiary butyl.

2. Claims: 17-32

Process for thermal chemical vapor deposition of a silicon nitride material on a substrate from a mixture comprising a N-containing chemical precursor and a Si-containing chemical precursor. The Si-containing chemical precursor contains less than 9.0% hydrogen atoms, by total weight.

3. Claims: 33-37

Method of controlling the properties of a PECVD-deposited silicon nitride material (low H content) from a halide-containing chemical precursor and a hydrogen source : SiH_nX_{4-n} .

ANNEX TO THE EUROPEAN SEARCH REPORT
ON EUROPEAN PATENT APPLICATION NO.

EP 01 30 3885

This annex lists the patent family members relating to the patent documents cited in the above-mentioned European search report. The members are as contained in the European Patent Office EDP file on The European Patent Office is in no way liable for these particulars which are merely given for the purpose of information.

26-10-2001

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EPO FORM P0459
For more details about this annex : see Official Journal of the European Patent Office, No. 12/82